WEST Search History

DATE: Tuesday, June 03, 2003

Set Name side by side	Query	Hit Count	Set Name result set
	DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ		
L36	L35 not L34	72	L36
L35	L32 and (polysilicon or (polycrystal$5 silicon) or SiN or SiNx or "SiN.sub.x" or (silicon nitride))	105	L35
L34	L33 not (L28 or L31)	67	L34
L33	L32 same (alter$5 or change or changed or changing or raise or raised or raising or increas$4 or lower$3 or decreas$4 or modif$8 or affect$4 or effect$3 or optimiz$7 or influenc$4)	67	L33
L32	((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	336	L32
L31	L30 not L28	7	L31
L30	L29 and (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen))	13	L30
L29	((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) same (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) same ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	145	L29
L28	((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	42	L28
	DB=USPT,PGPB; PLUR=YES; OP=ADJ		
L27	(polysilicon or (polycrystal$5 silicon) or SiN or SiNx or "SiN.sub.x" or (silicon nitride)) and ((SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)) with (RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)))	6	L27
L26	(polysilicon or (polycrystal$5 silicon) or SiN or SiNx or "SiN.sub.x" or (silicon nitride)) and ((SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4) or (index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)) with (RTA or	364	L26

anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)))

L25	L24 not (L22 or L19 or L17 or L15 or L13)	33	L25
L24	L23 and L9	64	L24
L23	(polysilicon or (polycrystal$5 silicon) or SiN or SiNx or "SiN.sub.x" or (silicon nitride)) and ((SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4) or (index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)) same (RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)))	1137	L23
L22	L21 not L16	81	L22
L21	((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)) with (alter$5 or change or changed or changing or raise or raised or raising or increas$4 or lower$3 or decreas$4 or modif$8 or affect$4 or effect$3 or optimiz$7 or influenc$4))	95	L21
L20	((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	497	L20
L19	L18 not (L15 or L17)	63	L19
L18	((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	79	L18
L17	L16 not L15	36	L17
L16	L9 and ((anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	42	L16
L15	L9 and ((RTA or anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	16	L15
L14	6410173.pn.	1	L14
L13	L12 and ((index near2 refract$4) or (extinction coefficient) or (optical propert$4))	26	L13
L12	L7 and L8	183	L12

L11	L10 and (anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4))	23	L11
L10	L6 and L7	66	L10
L9	L6 or L7 or L8	7684	L9
L8	(427/372.2).ccls. or (427/376.2).ccls. or ((427/397.7)!.CCLS.)	2814	L8
L7	(427/255.29).ccls. or (427/255.37).ccls. or (427/419.1).ccls. or (427/419.2).ccls. or (438/761).ccls. or (438/786).ccls. or (438/787).ccls. or (438/788).ccls. or (438/791).ccls. or (438/792).ccls. or ((438/29)!.CCLS.)	3364	L7
L6	(427/162).ccls. or (359/580).ccls. or (359/581).ccls. or ((359/586)!.CCLS.)	1801	L6

DB=JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

L5	(Chiou or Jang or (Taiwan Semiconductor)) and ((anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	1	L5
L4	(Chiou or Jang or (Taiwan Semiconductor)) and ((anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	7	L4

DB=USPT,PGPB; PLUR=YES; OP=ADJ

L3	(Chiou.in. or Jang.in. or (Taiwan Semiconductor).as.) and ((anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (SiON or SiONH or (silicon near2 oxynitride) or SiO2 or "SiO.sub.2" or (silicon $2oxide) or (silicon near2 oxygen near2 nitrogen near2 hydrogen)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	8	L3
L2	(Chiou.in. or Jang.in. or (Taiwan Semiconductor).as.) and ((anneal$3 or bake or baked or baking or (heat near2 treat$4) or (thermal$2 near2 treat$4)) with (ARC or DARC or BARC or (antireflect$4) or (anti reflect$4)) with ((index near2 refract$4) or (extinction coefficient) or n or k or (optical propert$4)))	1	L2
L1	6268294.pn. or 6020273.pn.	2	L1

END OF SEARCH HISTORY